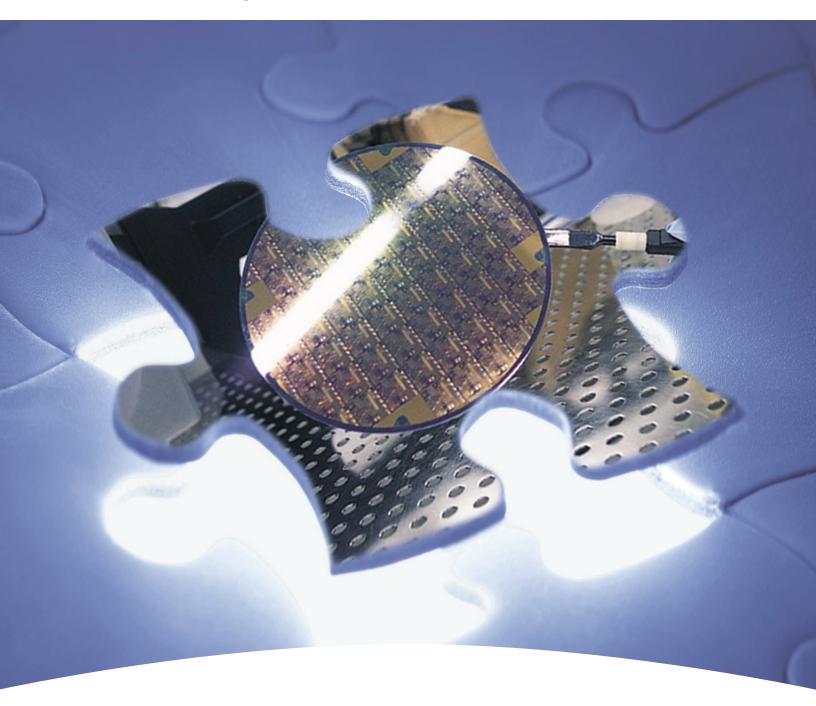
Electronic Polymers

Honeywell



Honeywell ACCUSPIN[®] Antimony (Sb-532) Spin-on Dopant

Honeywell ACCUSPIN® Antimony (Sb-532) Spin-on Dopant

POLYMER FOR N-TYPE BURIED LAYER DIFFUSION

BENEFITS

- Industry proven performance in bipolar devices
- Lower maintenance costs than antimony trioxide solid sources
- Better control of sheet resistance non-uniformity to within 1% within a wafer and 2% wafer to wafer
- Safer to handle and use than solid antimony sources

OVERVIEW

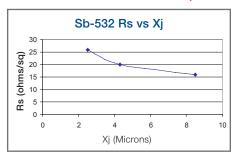
The ACCUSPIN Sb-532 Spin-on dopant is an antimony doped silicon oxide polymer designed for n-type buried layer diffusion. ACCUSPIN Sb-532 has been in large volume IC production for over 25 years.

Sb-532 can be applied using standard spin coaters. ACCUSPIN Sb-532 Spin-on dopant reduces the need for costly diffusion furnace tube cleaning or replacement required when using antimony trioxide dopants. ACCUSPIN Sb-532 materials also reduce any auto-doping from the furnace walls.

Because ACCUSPIN Sb-532 Spin-on dopant is an antimony bonded silicate polymer, diffusion is more uniform during the drive-in process so sheet resistance and junction depths are repeatable. The Spin-on process eliminates sheet resistance non-uniformity issues due to changes in gas flows of arsine or arsenic trioxide vaporization sources and wafer placement in the diffusion furnace.

FEATURES

Sheet Resistance vs Junction Depth



Thickness

Product	Thickness
Sb-532	800Å

Material Properties

Sb-532 Shelf Life @ 0-4°C: 6 months Bottle Sizes Available 125ml, 250ml, 500ml, 1L, 4L



Honeywell Electronic Materials

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